

STAGE APPARATUS, LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

ABSTRACT

In order to improve the productivity of a lithographic apparatus, a stage apparatus for holding two patterning devices is described. The patterning devices are arranged such that the distance between the patterns in the scanning direction corresponds to the length of the pattern in the scanning direction. By doing so, an improved exposure sequence may be performed by exposing a first die with a first pattern, skipping a second die adjacent to the first die, and exposing a third die adjacent to the second die using a second pattern.

Figures 2a – 2f